IN THE SPECIFICATION

Please replace the paragraph starting on line 11, page 8 with the following paragraph:

A first design rule used for manufacturing the first circuit region 11 is determined as a design rule where a wiring interval is, for example, Xµm suitable for using the high power supply voltage (for example, 3 Volts), and a second design rule used for manufacturing the second circuit region 12 is determined as a design rule where a wiring interval is, for example, Yµm (where, X > Y) suitable for using the low power supply voltage (for example, 1.2 Volts). Specifically, in the present invention, the semiconductor integrated circuit having a plurality of circuit regions where different power supply voltages are used is not manufactured by a single design rule, but the semiconductor integrated circuit is manufactured by a plurality of design rules corresponding to the plurality of circuit areas using different power supply voltages. Concretely, the semiconductor integrated circuit is not manufactured by a first design rule for manufacturing a first circuit region 11 using the high power supply voltage (3 Volts) and a second design rule for manufacturing a second circuit region 12 using the low power supply voltage (1.2 Volts).